

ABSTRACT

An embodiment of the instant invention is a method of oxidizing a first feature (feature 108 and/or feature 104 of FIGURE 1 and feature 314 of FIGURE 3) while leaving a second feature substantially unoxidized (features 110 and 112 of FIGURE 1 and features 310 and 312 of FIGURE 3), the method comprised of subjecting the first and second features to an oxygen-containing gas and a separate hydrogen-containing gas. Preferably, the oxygen-containing gas is comprised of a gas selected from the group consisting of: O_2 , N_2O , CO_2 , H_2O , and any combination thereof, and the hydrogen-containing gas is comprised of H_2 . The first feature is, preferably, comprised of polycrystalline silicon, silicon oxide, or a dielectric material, and the second feature is, preferably, comprised of tungsten.

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